AMENDMENTS TO THE CLAIMS

Please enter the following amendments:

1. (Currently Amended) A method of manufacturing a plasma display panel, in which a plurality of ~~structure~~ structures of the plasma display panel [[is]] are formed with photolithography, wherein at least one of the structures of the plasma display panel is exposed twice ~~in a process of forming the structure~~ using successive first and second exposures, and a photomask and the plasma display panel are [[is]] moved relative to each other within an allowable range of displacement in [[a]] an exposure pattern, between [[a]] the first and [[a]] second exposures.

2. (Currently Amended) A method of manufacturing a plasma display panel, in which a plurality of ~~structure~~ structures of the plasma display panel [[is]] are formed with photolithography, wherein at least one of the structures of the plasma display panel is exposed twice ~~in a process of forming the structure~~ using successive first and second exposures, and a photomask and the plasma display panel are [[is]] moved relative to each other by ~~at least one cycle~~ multiple cycles of periodicity included in [[a]] an exposure pattern, and also within an allowable range of displacement at the position, between [[a]] the first and [[a]] second exposures.

3. (New) The method according to claim 1, wherein each of the structures which is exposed twice extends primarily in a lengthwise direction, has a width w in a widthwise direction orthogonal to the lengthwise direction, and is disposed periodically with a pitch p.

4. (New) The method according to claim 3, wherein the photomask is moved a distance in the widthwise direction between the first and second exposures, the distance being less than w.

5. (New) The method according to claim 3, wherein the photomask is moved two or more integral times the distance p in the widthwise direction between the first and second exposures.

6. (New) The method according to claim 3, wherein the photomask is moved a distance in the lengthwise direction between the first and second exposures, the distance being less than p.

7. (New) The method according to claim 3, wherein the photomask is moved a distance in the lengthwise direction between the first and second exposures, the distance being less than w.

8. (New) The method according to claim 4, wherein the structures are address electrodes formed by exposing a photosensitive silver paste.

9. (New) The method according to claim 5, wherein the structures are address electrodes formed by exposing a photosensitive silver paste.

10. (New) The method according to claim 6, wherein the structures are address electrodes formed by exposing a photosensitive silver paste.

11. (New) The method according to claim 7, wherein the structures are address electrodes formed by exposing a photosensitive silver paste.